

Lianjia Wu

List of Publications by Year in descending order

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Version: 2024-02-01

15
papers

224
citations

1040056

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1125743

13
g-index

15
all docs

15
docs citations

15
times ranked

253
citing authors

#	ARTICLE	IF	CITATIONS
1	Complexation behavior of poly(acrylic acid) and lanthanide ions. <i>Polymer</i> , 2014, 55, 1183-1189.	3.8	40
2	Absorption coefficient of metal-containing photoresists in the extreme ultraviolet. <i>Journal of Micro/Nanolithography, MEMS, and MOEMS</i> , 2018, 17, 1.	0.9	28
3	Universal direct patterning of colloidal quantum dots by (extreme) ultraviolet and electron beam lithography. <i>Nanoscale</i> , 2020, 12, 11306-11316.	5.6	27
4	Mechanistic insights in Zr- and Hf-based molecular hybrid EUV photoresists. <i>Journal of Micro/Nanolithography, MEMS, and MOEMS</i> , 2019, 18, 1.	0.9	21
5	Tuning photoionization mechanisms of molecular hybrid materials for EUV lithography applications. <i>Journal of Materials Chemistry C</i> , 2019, 7, 33-37.	5.5	18
6	Unravelling the effect of fluorinated ligands in hybrid EUV photoresists by X-ray spectroscopy. <i>Journal of Materials Chemistry C</i> , 2020, 8, 14757-14765.	5.5	18
7	Hybrid EUV Resists with Mixed Organic Shells: A Simple Preparation Method. <i>European Journal of Inorganic Chemistry</i> , 2019, 2019, 4136-4141.	2.0	16
8	Photo-induced Fragmentation of a Tin-oxo Cage Compound. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2018, 31, 243-247.	0.3	15
9	Fluorescent Labeling to Investigate Nanopatterning Processes in Extreme Ultraviolet Lithography. <i>ACS Applied Materials & Interfaces</i> , 2021, 13, 51790-51798.	8.0	10
10	Absorption coefficient and exposure kinetics of photoresists at EUV. <i>Proceedings of SPIE</i> , 2017, , .	0.8	8
11	UV and VUV-induced fragmentation of tin-oxo cage ions. <i>Physical Chemistry Chemical Physics</i> , 2021, 23, 20909-20918.	2.8	8
12	Bottom-Up Nanofabrication with Extreme-Ultraviolet Light: Metal-Organic Frameworks on Patterned Monolayers. <i>ACS Applied Materials & Interfaces</i> , 2021, 13, 43777-43786.	8.0	5
13	Ti, Zr, and Hf-based molecular hybrid materials as EUV photoresists. , 2018, , .		5
14	The role of the organic shell in hybrid molecular materials for EUV lithography. , 2019, , .		3
15	Extreme ultraviolet-excited time-resolved luminescence spectroscopy using an ultrafast table-top high-harmonic generation source. <i>Review of Scientific Instruments</i> , 2021, 92, 113004.	1.3	2